Amendments to the Claims

Listing of Claims:

This listing of claims will replace all prior versions, and listings, of claims in the application:

- 1. (Currently Amended) A method of treating a cathode of an OLED device having a substrate and which has a spaced anode and organic layers between the anode and cathode, comprising:
- a) evacuating a chamber so that it has a pressure no greater than 10⁻⁶ Torr:
- b) heating the OLED substrate in the chamber to a temperature less than 100°C; and
- c) delivering gas, including ozone, to the evacuated chamber which includes the heated OLED substrate at a sufficient rate so that the pressure to increase the pressure in the chamber to a level that is less than 1 atmosphere, so that the life of the OLED substrate is increased and the operating voltage is decreased.
- 2. (Original) A method of forming an OLED device, comprising:
 - a) providing an anode over the substrate;
 - b) providing a series of organic layers over the substrate; and
- c) providing a cathode having at least two sublayers by forming a first cathode sublayer on the organic layers and treating the first cathode sublayer in accordance with the method according to claim 1, and forming a second cathode sublayer on the first cathode sublayer.
- 3. (Original) The method according to claim 1 wherein the ozone gas concentration is between the range of 10-20% by volume of the incoming gas and the substrate temperature is below the glass transition temperature of at least one of the deposited organic materials on the OLED device.

- 4. (Original) The method according to claim 2 wherein the ozone gas concentration is between the range of 10-20% by volume of the incoming gas and the substrate temperature is below the glass transition temperature of at least one of the deposited organic materials on the OLED device.
- 5. (Original) A method of forming an OLED device, comprising:
 - a) providing a substrate and an anode over the substrate;
 - b) providing a series of organic layers over the substrate;
 - c) providing a cathode over the substrate;
 - d) performing the method according to claim 1; and
- e) forming by an atomic layer deposition process an encapsulation layer using alternating gases, at least one of which has ozone.